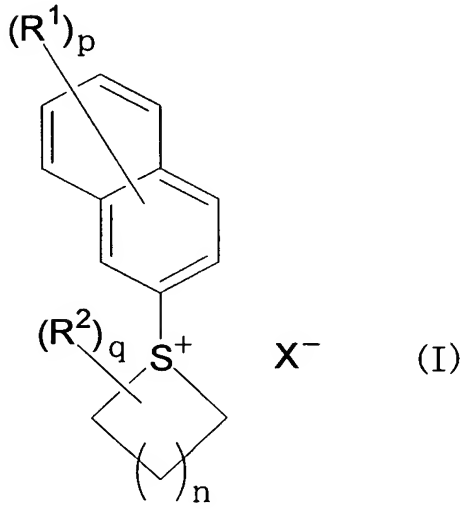
## ABSTRACT OF THE DISCLOSURE

A sulfonium salt compound excelling in transparency to deep ultraviolet rays at a wavelength of 220 nm or less, exhibiting well-balanced excellent performance such as sensitivity, resolution, pattern form, LER, and storage stability when used as a photoacid generator, a photoacid generator comprising the sulfonium salt compound, and a positive-tone radiation-sensitive resin composition containing the photoacid generator.

The sulfonium salt compound is shown by the following formula (I),



(I)

wherein $R^1$ represents a halogen atom, an alkyl group, a monovalent alicyclic hydrocarbon group, an alkoxyl group, or $-OR^3$ group, wherein $R^3$ is a monovalent alicyclic hydrocarbon group, $R^2$ represents a (substituted)-alkyl group or two or more $R^2$ groups form a cyclic structure, p is 0-7, q is 0-6, n is 0-3, and $X^-$ indicates a sulfonic acid anion.

The positive-tone radiation-sensitive resin composition comprises (A) a photoacid generator of the sulfonium-salt compound and (B) an acid-dissociable group-containing resin.